

EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	4690	(wafer substrate) and (collector.ti. collector.ab. collector.clm.) and (exhaust\$4 vacuum\$4)	US-PGPUB; USPAT	OR	ON	2010/08/25 19:02
S2	932	(wafer substrate) and (collector.ti. collector.ab. collector.clm.) and ((exhaust\$4 vacuum\$4) with (rate\$4 flow\$4 speed\$4 velocity))	US-PGPUB; USPAT	OR	ON	2010/08/25 19:03
S3	8	(wafer substrate) and ("liquid collector".ti. "liquid collector".ab. "liquid collector".clm.) and ((exhaust\$4 vacuum\$4) with (rate\$4 flow\$4 speed\$4 velocity))	US-PGPUB; USPAT	OR	ON	2010/08/25 19:04
S4	14	(wafer substrate) and ("liquid collector".ti. "liquid collector".ab. "liquid collector".clm.) and (exhaust\$4 vacuum\$4)	US-PGPUB; USPAT	OR	ON	2010/08/25 19:07
S5	6	S4 not S3	US-PGPUB; USPAT	OR	ON	2010/08/25 19:07
S6	31	(wafer substrate) and ("liquid collector".ti. "liquid collector".ab. "liquid collector".clm.)	US-PGPUB; USPAT	OR	ON	2010/08/25 19:08
S7	17	S6 not (S4 S3)	US-PGPUB; USPAT	OR	ON	2010/08/25 19:08
S8	179944	(wafer substrate) and ((exhaust\$4 vacuum\$4 flow\$4) with pressure)	US-PGPUB; USPAT	OR	ON	2010/08/25 19:12
S9	4029	(wafer substrate) and (((exhaust\$4 vacuum\$4 flow\$4) with pressure) with equal)	US-PGPUB; USPAT	OR	ON	2010/08/25 19:13
S10	211	(wafer substrate) and (((exhaust\$4 vacuum\$4 flow\$4) with pressure) with equal) and (collect\$4 with liquid)	US-PGPUB; USPAT	OR	ON	2010/08/25 19:13
S11	211	S10 not (S6 S4 S3)	US-PGPUB; USPAT	OR	ON	2010/08/25 19:13
S12	580	(wafer substrate) and (((exhaust\$4 vacuum\$4 flow\$4) with pressure) with "same") and (collect\$4 with liquid)	US-PGPUB; USPAT	OR	ON	2010/08/25 19:48
S13	527	S12 not (S11 S6 S4 S3)	US-PGPUB; USPAT	OR	ON	2010/08/25 19:48
S14	514	(wafer substrate) and (collector) and (exhaust\$4 vacuum\$4)	FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/08/25 21:33
S15	584	(wafer substrate) and levels! and (exhaust\$4 vacuum\$4)	FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/08/26 09:04

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S16	514	(wafer substrate) and (collector) and (exhaust\$4 vacuum\$4)	FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/08/26 09:04
S17	574	S15 not S16	FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2010/08/26 09:04
S18	24	(wafer substrate) and levels! and collect\$4	JPO	OR	ON	2010/08/26 10:12
S19	12274	(wafer substrate) and collect\$4	JPO	OR	ON	2010/08/26 10:19
S20	1284	(wafer substrate) and levels!	JPO	OR	ON	2010/08/26 10:19
S21	64	(wafer substrate) and levels! and drain\$4	JPO	OR	ON	2010/08/26 10:19
S23	7	"recovery cup"	JPO	OR	ON	2010/08/26 10:30
S24	55	"recovery cup"	US-PGPUB; USPAT; USOCR; FPRS; EPO; DERWENT; IBM_TDB	OR	ON	2010/08/26 10:39
S25	2	"4903717".PN.	US-PGPUB; USPAT; USOCR; FPRS; EPO; DERWENT; IBM_TDB	OR	ON	2010/08/26 11:00
S26	951	((semiconductor or substrate or wafer) near5 (coat\$4 or wash or washed or washer or washing or clean or cleaner or cleaning or cleaned or decontaminat\$4 or rins\$4 or etch\$4) near5 (acid or etchant or water or liquid or solution) near5 (spin\$4 or rotary or rotat\$4 or revolv\$4)) and ((inner or first or inside or interior) near5 (bowl or container or receptacle or basin or vessel or chamber or enclosure or compartment or cup)) and ((outer or second or outside or exterior) near5 (bowl or container or receptacle or basin or vessel or chamber or enclosure or compartment or cup)) and ((bowl or container or receptacle or basin or vessel or chamber or enclosure or compartment) near5 (drain\$4 or empty\$4 or outlet or exhaust\$4 or discharg\$4 or evacuat\$4))	US-PGPUB; USPAT	OR	ON	2010/08/26 12:06

EAST Search History (I nterference)

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Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S27	624	(wafer substrate) and levels! and (((exhaust\$4 vacuum\$4 flow\$4) with pressure) with equal)	USPAT; UPAD	OR	ON	2010/08/26 16:07
S28	522	((semiconductor or substrate or wafer) near5 (coat\$4 or wash or washed or washer or washing or clean or cleaner or cleaning or cleaned or decontaminat\$4 or rins\$4 or etch\$4) near5 (acid or etchant or water or liquid or solution) near5 (spin\$4 or rotary or rotat\$4 or revolv\$4)) and ((inner or first or inside or interior) near5 (bowl or container or receptacle or basin or vessel or chamber or enclosure or compartment or cup)) and ((outer or second or outside or exterior) near5 (bowl or container or receptacle or basin or vessel or chamber or enclosure or compartment or cup)) and ((bowl or container or receptacle or basin or vessel or chamber or enclosure or compartment) near5 (drain\$4 or empty\$4 or outlet or exhaust\$4 or discharg\$4 or evacuat\$4)) and ((exhaust\$4 vacuum\$4 flow\$4) with pressure)	US-PGPUB; USPAT; UPAD	OR	ON	2010/08/26 16:41
S29	521	S28 not S27	US-PGPUB; USPAT; UPAD	OR	ON	2010/08/26 16:42
S30	411	(wafer substrate) and (levels! with (exhaust\$4 vacuum\$4 flow\$4)).clm.	USPAT; UPAD	OR	ON	2010/08/26 16:51